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IN THE UNITED STATES PATENT & TRADEMARK OFFICE

IN RE APPLICATION OF

HIROSHI SHIHO, ET AL. : EXAMINER: CHEN, KIN CHAN

SERIAL NO: 10/529,742

FILED: JANUARY 6, 2006 : GROUP ART UNIT: 1765

FOR: POLISHING PAD FOR
SEMICONDUCTOR WAFER AND
LAMINATED BODY FOR POLISHING OF
SEMICONDUCTOR WAFER EQUIPPED
WITH THE SAME AS WELL AS
METHOD FOR POLISHING OF
SEMICONDUCTOR WAFER

REQUEST FOR RECONSIDERATION

COMMISSIONER FOR PATENTS ALEXANDRIA, VIRGINIA 22313

SIR:

Responsive to the Office Action of June 8, 2007, Applicants request reconsideration in view of the following remarks.

Remarks begin on page 2 of this paper.